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## PATENT ABSTRACTS OF JAPAN

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(71) Applicant: MITSUBISHI KASEI CORP

(72) Inventor: FUJIWARA SUMIMARU  
 TAKEMURA KAZUNARI  
 TSUCHIYA ATSUSHI(54) SPUTTERING TARGET AND ITS  
 PRODUCTION

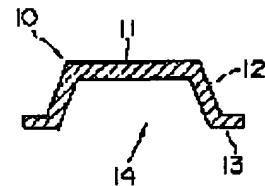
## (57) Abstract:

PURPOSE: To prevent the separation of the target part from the supporting part of a sputtering target.

CONSTITUTION: The target part 11 and supporting part of a sputtering target 10 are integrated by deep drawing. Consequently, the target part 11 is not separated in sputtering, a leakage due to pinholes, etc., is prevented, the material yield is increased, and the cost is reduced. A clearance is partly formed between

a blank and a die in deep drawing to relieve the stress exerted on the target part in deep drawing, hence the crystal characteristic is not changed, and the target characteristic is improved.

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